ELAN



WILAPLAT Electroforming Baths

High Performance Electroforming Bright Copper Bath For Electroforming Article No. 3060400202

Description	Very ductile, bright, almost crack and stress-free layering is achieved with this sulphuric acid Copper Bath. Its high levelling power means that pre- polishing of the work pieces is not essential. Due to the thus significantly reduced surface roughness, this layer can be considered as a universal foundation for decorative coating in precious metals.	
Application	The Copper Bath is for use in a conventional electro-plating unit such as the WILAPLAT-System. For extended process times (approx. 4Ah/litre) brightening agents must be added. The amount of brightening agent added depends on the extent to which the brightness has diminished. The ration between brightener 408 and 801 must be 1 : 3.5 (1 ml of brightener no. 408 means 3.5 ml of brightener no. 801 must be added). For larger bath volumes air injection is recommended as this will increase the anode solubility.	
Operating Data	Copper Content	50-60 a/l
J	Sulphuric Acid Content	50-65 g/l
	Temperature	20-30°C
	Voltage	0.3-1.6 volts
	Current Density	1.0-6.0 dm ²
	pH Value	<1
	Movement	Movement of electrolyte or work pieces required
	Anodes	Phosphorous Copper
	Tank Material	Glass, porcelain, plastic (PE, PVC etc.)
Deposition Data	Allov Deposit	99 8% Cu
	Hardness	approx. 220 HV
	Deposition Rate	1.18 g/Ah
	Density	8.9 g/cm ³
	Current Output	100%
	Bath Density	1.17 g/cm ³





THE ESSENTIAL PART OF YOUR SOLUTION

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Supply Form	Ready for use solution
Regeneration	Not worthwhile
Warning!	Chemicals and materials used in electro-plating techniques can be corrosive or poisonous. During use, storage, transportation and disposal the relevant guidelines must be observed. For further information see the EEC Safety Data Sheets